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XII	"Minimizing PFC Emissions From Existing", Johnson, et al, SEMICON WEST 2000.  "Electrical Optimization of Plasma-enhanced Chemical" Sobolewski, et al, J. Vac. Sci. Technol. B 16(1),													
10		"El	ectrica	al Opti	mizat	on of	Plasm	a-enhance	d Chemical" Sobolewski,	et al, J. Vac. S	sci. Technol.	D 10(1),		
X2		1998.  "Reduction of PFC Emissions by Gas Circulation Cleaning", R. Nakata, et al, IEEEE Int'l Sym, No.												
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